

Attorney Docket No.: 0180151

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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

JAN 22 2008

In re Application of: **Labelle, et al.**

Serial No.: 10/705,347

Filed: 11/08/2003

For: **Method for Integrating a High-K Gate Dielectric in a Transistor Fabrication Process**

Art Unit: 1792

Examiner: Chen, Kin Chan

RESPONSE TO FINAL OFFICE ACTION

*Reconsideration only.*

Mail Stop AF  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

*KCC 1/25/08*

Dear Sir/Madam:

This is in response to the *Final Office Action* dated November 19, 2007 in the above-referenced patent application. Please enter and consider the following remarks.